



Robert Greene Sterne
Edward J. Kessler
Jorge A. Goldstein
David K.S. Cornwell
Robert W. Esmond
Tracy-Gene G. Durkin
Michele A. Cimbala
Michael B. Ray
Robert E. Sokohl
Eric K. Steffe
Michael Q. Lee
Steven R. Ludwig
John M. Covert
Linda E. Alcorn
Robert C. Milonig
Lawrence B. Bugalsky
Donald J. Featherstone
Michael V. Messinger

Judith U. Kim
Timothy J. Shea, Jr.
Patrick E. Garrett
Heidi L. Kraus
Edward W. Yee
Albert L. Ferro*
Donald R. Banowitz
Peter A. Jackman
Teresa U. Medler
Jeffrey S. Weaver
Kendrick P. Patterson
Vincent L. Capuano
Eldora Ellison Floyd
Thomas C. Fiala
Brian J. Del Buono
Virgil Lee Beaston
Kimberly N. Reddick
Theodore A. Wood

Elizabeth J. Haanes
Joseph S. Ostroff
Frank R. Cottingham
Christine M. Lhulier
Rae Lynn Prengaman
Jane Shershenovich*
Lawrence J. Carroll*
George S. Bardmesser
Daniel A. Klein*
Jason D. Eisenberg
Michael D. Specht
Andrea J. Kamage
Tracy L. Muller*
LuAnne M. DeSantis
John J. Figueroa
Ann E. Summerfield
Tiera S. Coston*
Aric W. Ledford*

Michael D. Specht
Jessica L. Parezo
Timothy A. Doyle*
Cynthia M. Bouchez
Nicole D. Dretar*
Ted J. Ebersole
Registered Patent Agents*
Karen R. Markowicz
Nancy J. Leith
Helene C. Carlson
Gaby L. Longworth
Matthew J. Dowd
Aaron L. Schwartz
Mary B. Tung
Katrina Y. Pei Quach
Bryan L. Skelton
Robert A. Schwartzman

Teresa A. Colella
Jeffrey S. Lundgren
Victoria S. Rutherford
Eric D. Hayes
Michelle K. Holoubek
Robert H. DeSelms
Simon J. Elliott
Julie A. Heider
Mita Mukerjee
Scott M. Woodhouse
Of Counsel
Kenneth C. Bass III
Evan R. Smith
Marvin C. Guthrie
*Admitted only in Maryland
*Admitted only in Virginia
*Practice limited to
Federal Agencies

February 24, 2004

WRITER'S DIRECT NUMBER:
(202) 772-8678

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Mail Stop Patent Application

Re: U.S. Non-Provisional Utility Patent Application under 37 C.F.R. § 1.53(b)
Appl. No. *To Be Assigned*; Filed: February 24, 2004
For: **Novel Monomers Containing an Oxepan-2-One Group, Photoresist
Compositions Comprising Polymers Prepared from the Monomers,
Methods for Preparing the Compositions, and Methods for Forming
Photoresist Patterns Using the Compositions**

Inventors: KIM *et al.*
Our Ref: 2236.0090000/JUK/SMW

Sir:

The following documents are forwarded herewith for appropriate action by the U.S. Patent and Trademark Office:

1. PTO Utility Patent Application Transmittal (Form PTO/SB/05);
2. U.S. Utility Patent Application entitled:

**Novel Monomers Containing an Oxepan-2-One Group, Photoresist
Compositions Comprising Polymers Prepared from the Monomers, Methods
for Preparing the Compositions, and Methods for Forming Photoresist
Patterns Using the Compositions**

and naming as inventors:

Jin-Baek KIM, Tae-Hwan OH, Jae-Hak CHOI and Jae-Jun LEE;

the application consisting of:

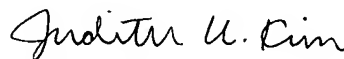
- a. An Application Data Sheet (37 C.F.R. § 1.76);
- b. A specification containing:

- i. 32 pages of description prior to the claims;
 - ii. 8 pages of claims (32 claims);
 - iii. a one (1) page abstract;
- c. 1 sheet of drawings: (Figure 1); and
- 3. Authorization to Treat a Reply As Incorporating An Extension of Time Under 37 C.F.R. § 1.136(a)(3);
- 4. Claim to Priority under 35 U.S.C. § 119(a)-(d);
- 5. A certified copy of Korean Patent Application No. 10-2003-0058525, filed August 23, 2003, priority of which is hereby claimed; and
- 6. Two (2) return postcards.

It is respectfully requested that, of the two attached postcards, one be stamped with the filing date of these documents and returned to our courier, and the other, prepaid postcard, be stamped with the filing date and unofficial application number and returned as soon as possible. The U.S. Patent and Trademark Office is hereby authorized to charge any fee deficiency, or credit any overpayment, to our Deposit Account No. 19-0036.

Respectfully submitted,

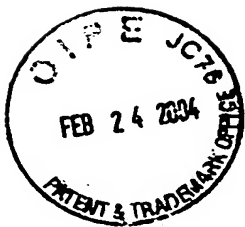
STERNE, KESSLER, GOLDSTEIN & FOX P.L.L.C.



Judith U. Kim
Attorney for Applicants
Registration No. 40,679

Enclosures

233467-1



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

KIM *et al.*

Appl. No.: *To Be Assigned*

Filed: February 24, 2004

For: **Novel Monomers Containing an Oxepan-2-One Group, Photoresist Compositions Comprising Polymers Prepared from the Monomers, Methods for Preparing the Compositions, and Methods for Forming Photoresist Patterns Using the Compositions**

Confirmation No.: *To Be Assigned*

Art Unit: *To Be Assigned*

Examiner: *To Be Assigned*

Atty. Docket: 2236.0090000/JUK/SMW

**Authorization to Treat a Reply as Incorporating an
Extension of Time Under 37 C.F.R. § 1.136(a)(3)**

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

The U.S. Patent and Trademark Office is hereby authorized to treat any concurrent or future reply that requires a petition for an extension of time under this paragraph for its timely submission, as incorporating a petition for extension of time for the appropriate length of time. The U.S. Patent and Trademark Office is hereby authorized to charge all required extension of time fees to our Deposit Account No. 19-0036, if such fees are not otherwise provided for in such reply.

Respectfully submitted,

STERNE, KESSLER, GOLDSTEIN & FOX P.L.L.C.

Judith U. Kim
Attorney for Applicants
Registration No. 40,679

Date: February 24, 2004

1100 New York Avenue, N.W.
Washington, D.C. 20005-3934
(202) 371-2600

Addendum

1. Novel Monomers Containing an Oxepan-2-One Group, Photoresist Compositions Comprising Polymers Prepared from the Monomers, Methods for Preparing the Compositions, and Methods for Forming Photoresist Patterns Using the Compositions
2. Korea Advanced Institute of Science and Technology